LISTING OF CLAIMS

No amendments to the claims are made by this Response. For the Examiner's convenience, a complete listing of claims is provided below.

1-5. (Withdrawn)

6. (Previously Presented) A method for generating a lithography mask, comprising:

generating integrated circuit design data;

analyzing the integrated circuit design data to generate context information for features of a mask without the use of tags; and

using the context information to write the mask features.

7. (Previously Presented) The method of claim 6, wherein using context information comprises:

analyzing the mask features for contextual priority.

8. (Original) The method of claim 7, wherein using context information comprises:

assigning priorities to the mask features.

9. (Original) The method of claim 8, wherein assigning priorities to the mask features comprises:

applying criteria to mask design data by manual process.

10. (Original) The method of claim 8, wherein assigning priorities to the mask features comprises:

applying criteria to mask design data by computer-aided automated process.

11. (Previously Presented) The method of claim 6, wherein using context information comprises:

analyzing mask features to determine circuit elements expected to be produced by a lithography system at a chip wafer surface.

12. (Original) The method of claim 6, further comprising:

configuring a mask design database to include additional contextual mask design data

generated in using the contextual information from the integrated circuit design data.

13. (Previously Presented) The method of claim 12, further comprising:

configuring the mask design database to optimize a write order for use by a mask writing

system.

14. (Original) The method of claim 6, wherein using context information comprises:

passing context information to a mask writing system.

15. (Original) The method of claim 6, wherein using context information comprises:

controlling a mask writing system based on the context information.

16-36. (Withdrawn)